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*4th International Symposium on  
Advanced Optical Manufacturing  
and Testing Technologies*

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## ***Design, Manufacturing, and Testing of Micro- and Nano-Optical Devices and Systems***

**Sen Han  
Masaomi Kameyama  
Xiangang Luo**  
*Editors*

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## Introduction

Optical manufacturing technology has achieved tremendous progress, especially during the last 20 years both in China and abroad. To meet the demand of the development in this area, AOMATT-International Symposium on Advanced Optical Manufacturing and Testing Technology has been held four times from 2000 to 2008. The 4th International Symposium on Advanced Optical Manufacturing and Testing Technology (AOMATT08) was held at Wang Jiang Hotel in Chengdu, China, 19–21 November 2008. A total of 381 papers have been selected for publication in the Proceedings of SPIE volumes 7281, 7282, 7283 and 7284, corresponding to the four conferences of AOMATT08: Large Mirrors and Telescopes; Advanced Optical Manufacturing Technologies; Optical Test and Measurement Technology and Equipment; and Design, Manufacturing, and Testing of Micro- and Nano-Optical Devices and Systems. We have faced many challenges during the organization of AOMATT08. They include the big Sichuan Wenchuan earthquake on 12 May 2008, the worldwide financial crisis, and the deepening recession in many countries around the world. These challenges and difficulties have negatively impacted the number of papers and attendees for AOMATT08. The number of accepted papers decreased from 485 for AOMATT07 to 381 for AOMATT08. However, conference quality has continued to improve. Based on comments from authors and attendees, significant improvements have been made in conference organization, the opening ceremony, quality of the plenary presentation, oral presentations, workshops, and the closing ceremony, etc. A more important fact is the continued improvement in the quality of the papers published in the Proceedings of SPIE. Many papers report cutting-edge research and development; more authors are from famous universities, research institutions, and leading enterprises around the world. Authors and attendees had the opportunity to exchange ideas and learn from each other at the conference.

We are delighted that each AOMATT symposium is more successful than the previous one. It has become a well-established symposium covering advanced optical manufacturing and testing technologies, and has attracted a loyal following in academy and industries around the world. Our goal is to develop AOMATT into a must-attend international symposium for the optical manufacturing and testing community. We would like to express our sincere appreciation to COS—The Chinese Optical Society, IOE—Institute of Optics and Electronics, Chinese Academy of Sciences, and to SPIE for sponsoring AOMATT08. We want to thank authors and attendees for attending the symposium and sharing their research with their colleagues around the world. We especially thank IOE and Dr. Yudong Zhang, President of IOE, for hosting AOMATT08 and the tremendous hospitality during the conference.

The world is in the middle of significant financial and economic crisis. Crisis often brings difficulties and opportunities at the same time. Many countries have

announced economic stimulus measures. The Chinese government has promised 600 billion Yuan RMB to six key national projects. Several projects are closely related to optical manufacturing and testing technology and equipments and represent opportunities for researchers and enterprises around the world. New discoveries and products will emerge as a result. We are looking forward to seeing you all at the AOMATT 2010 in China, please watch the SPIE and IOE websites for call for papers and exact time and locations.

**Li Yang**

Secretary General, AOMATT 2008

Chairman, Committee on Optical Manufacturing Technology (COMT), COS